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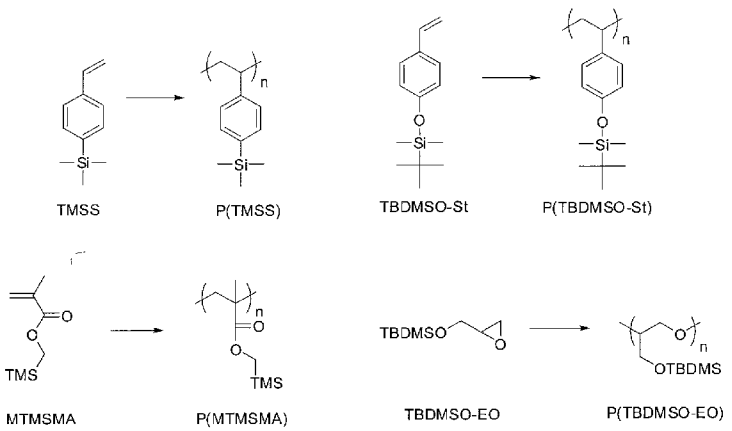
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(54) **Title**: USING CHEMICAL VAPOR DEPOSITED FILMS TO CONTROL DOMAIN ORIENTATION IN BLOCK COPOLYMER THIN FILMS

FIGURE 1



(57) **Abstract**: The present invention uses vacuum deposited thin films of material to create an interface that non-preferentially interacts with different domains of an underlying block copolymer film. The non-preferential interface prevents formation of a wetting layer and influences the orientation of domains in the block copolymer. The purpose of the deposited polymer is to produce nanostructured features in a block copolymer film that can serve as lithographic patterns.

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